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| 2 | BRS | L2 | 31 | 1 same nano\$8 | USPAT; US-PGP UB; EPO; JPO; DERWEN T; IBM_TD B | 2004/03/23 16:18 |
| 3 | BRS | L3 | 49969 | (lift-off or liftoff or (lift\$3 adj off)) | USPAT; US-PGP UB; EPO; JPO; DERWEN T; IBM_TD B | 2004/03/23 16:19 |
| 4 | BRS | L4 | 434 | 1 and 3 | USPAT; US-PGP UB; EPO; JPO; DERWEN T; IBM_TD B | 2004/03/23 16:19 |
| 5 | BRS | L5 | 890613 | residu\$6 | USPAT; US-PGP UB; EPO; JPO; DERWEN T; IBM_TD B | 2004/03/23 16:19 |

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```
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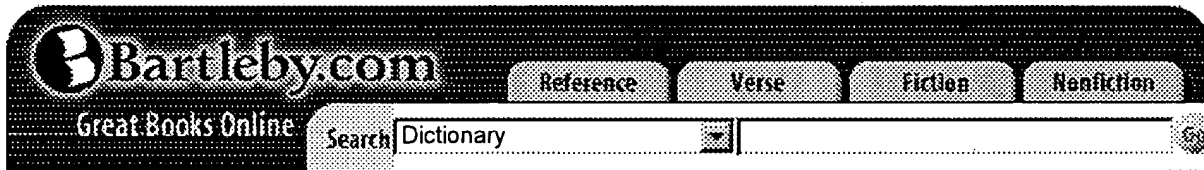
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multi—

PREFIX: **1.** Many; much; multiple: *multicolored*. **2a.** More than one: *multiparous*. **b.** More than two: *multilateral*.

ETYMOLOGY: Middle English, from Old French, from Latin, from *multus*, much, many.
See *mel-*² in Appendix I.

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